

반도체 공정용 RFG 개발사례

(주)뉴파워플라즈마
전원연구소

2017. 07. 05.

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1 >> 반도체 공정용 RF Generator 개요

2 >> 구성 및 설계

3 >> 실험 결과

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반도체 공정용 RF Generator 용도

반도체 전 공정 중, 핵심 공정인 화학기상증착(Chemical Vapor Deposition) 및 건식 식각(Dry Etch) 공정에서 **플라즈마를 발생시키기 위한 핵심 장비**임

반도체 제조 공정

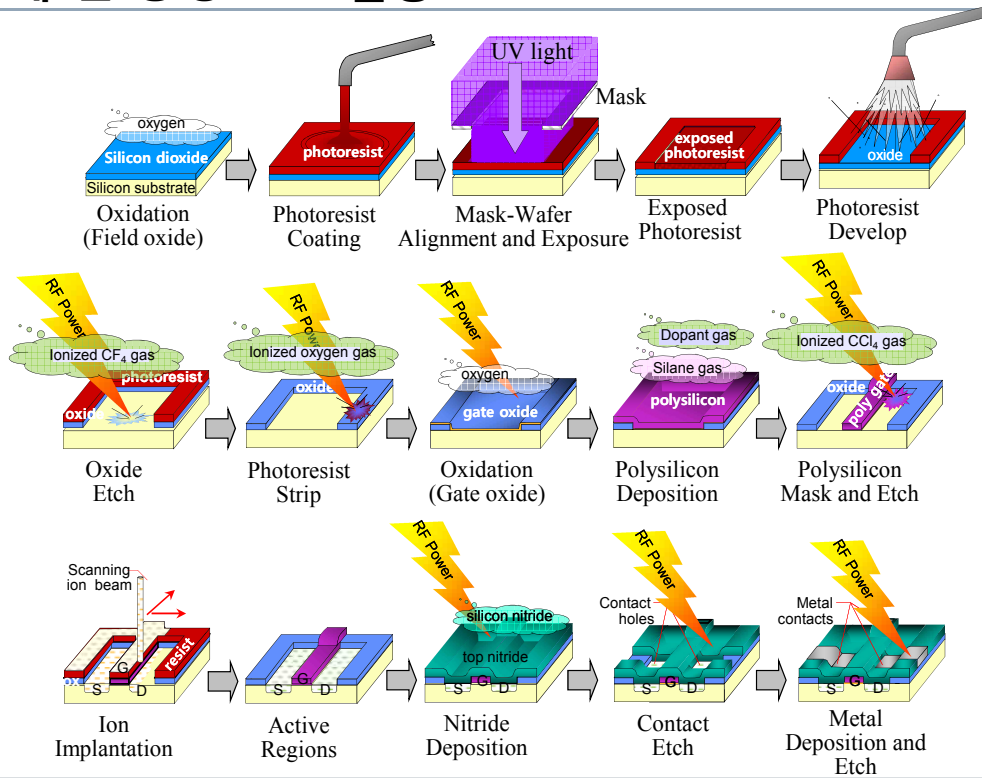


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반도체 전 공정 RFG 활용



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RFG 관련 반도체 장비시장 전망

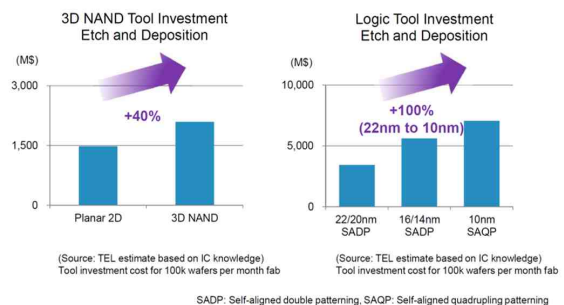
전 공정 장비 시장 예측



자료 : SEMI, 2015

공정 변화에 따른 증착, 식각 장비 수요 전망

▶ Multi-patterning and 3D devices such as 3D NAND and FinFET need more etch and deposition equipment



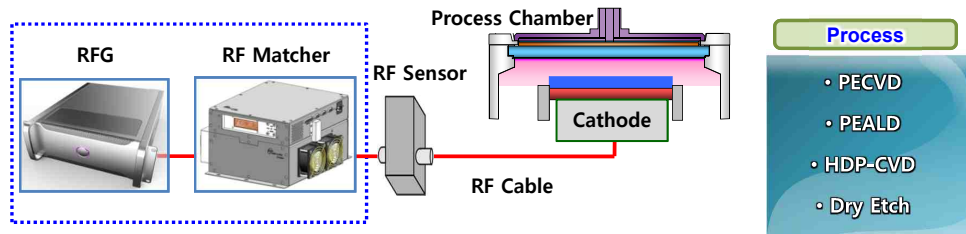
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반도체 공정용 RFG System 구성

장비 구성



RFG : 플라즈마 발생 용 RF Power 공급 및 제어

Matcher : Chamber 와 RFG의 임피던스 매칭

Process Chamber : 플라즈마 발생, 각 제조 공정 수행

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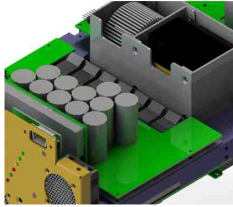
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RFG 핵심 설계 기술

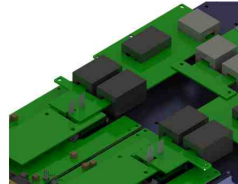
Power conversion



S.M.P.S design

Inductor ,transformer design
Analog circuit design
DSP firmware programming
PID control design
Interface system design
Switching noise reduction

RF Power AMP



RF circuit design

RF sensor design
High frequency transformer design
High frequency inductor design
High frequency inverter design
RF noise reduction

Digital control



Analog circuit design

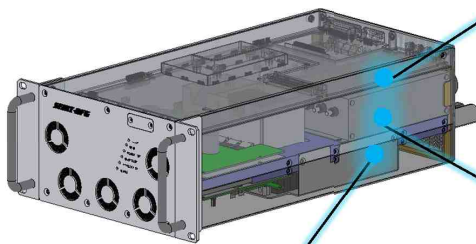
Logic circuit design
RF Detector design
Signal generation
FPGA design
DSP firmware programming
PID control design
U.I PC software programming

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반도체 공정용 RFG 개발 사양



Digital control

- Fast response PID control with dual DSP
- High accuracy output PID control with dual DSP
- System monitoring and abnormal protection
- D.D.S and signal process with FPGA
- Industrial standard interface
(Profibus , EtherCAT, Devicenet,RS-232)

Power conversion

- High power density and compact design
- High efficiency , High power factor
- Fast response for dynamic load
- Compliance SAG-22 , CE ,UL

RF Power AMP

- Low noise and distortion
- Wide range power output control
- High power density and high efficiency

Topology

- Half bridge inverter
- Full bridge inverter
- Push-pull inverter
- High frequency ,high power LC filter

Topology

- Buck ,Boost converter
- Cascade Buck-boost converter
- Resonant converter
- Active or passive PFC

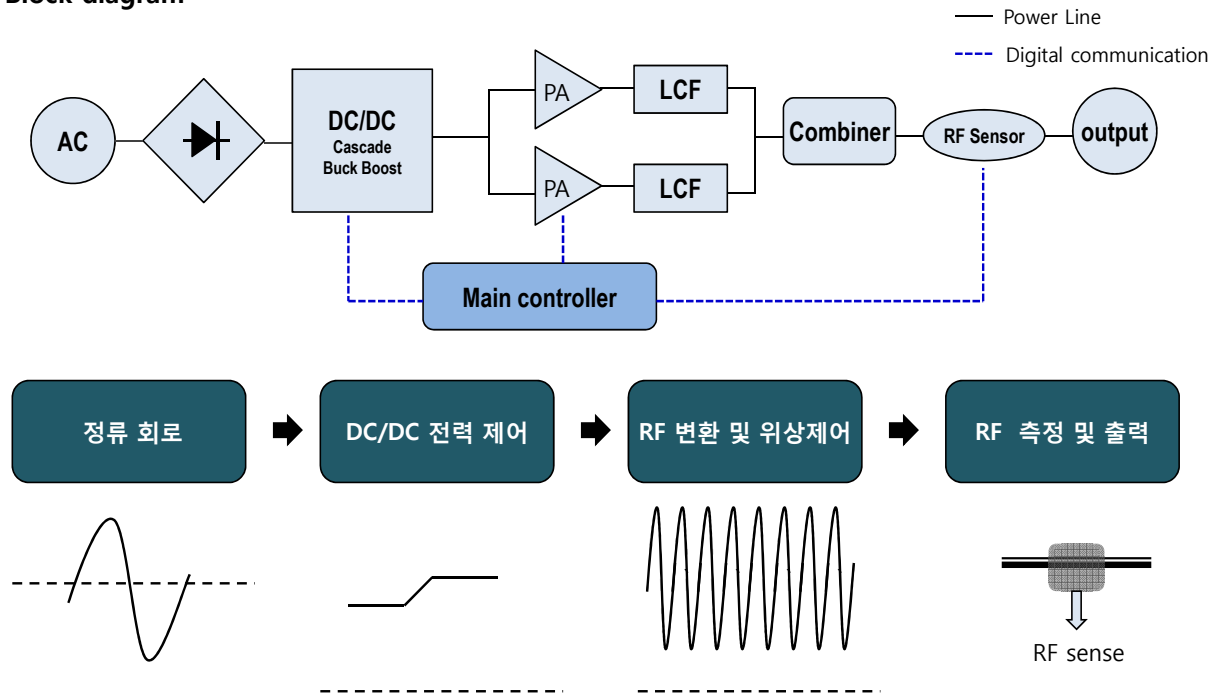
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RFG 설계 구성

Block diagram



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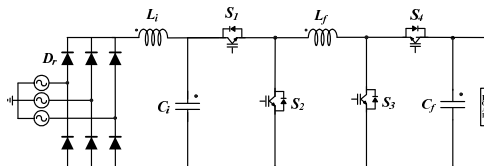
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RFG H/W 설계

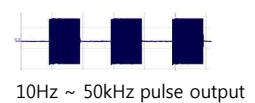
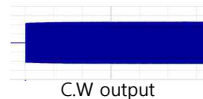
DC/DC

Input : AC ,3 Φ 187V ~ 240V
 Output : DC 75~ 300V ,3.5kW
 Topology : Cascade Buck-Boost
 with synchronous rectification
 Regulation : $\leq 1\%$
 Turn on & rise time: $\leq 10\text{ms}$
 Efficiency : $\geq 95\%$

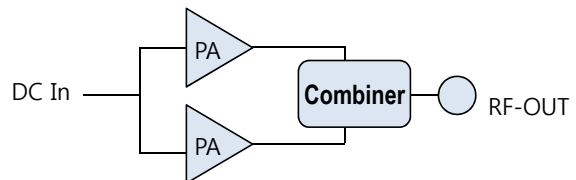


Power AMP

Output : 13.56MHz
 Output range : 1W ~ 3kW
 Output impedance : 50ohm
 Output type:



Topology : Full bridge inverter
 Efficiency : $\geq 88\%$



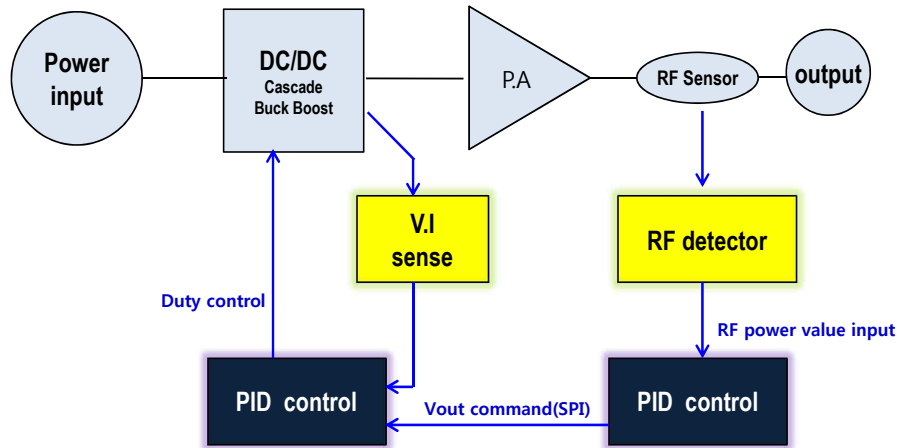
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RFG control system 설계

제어 개념도



제어 최종 목표 : Pulse /Continuous RF output power

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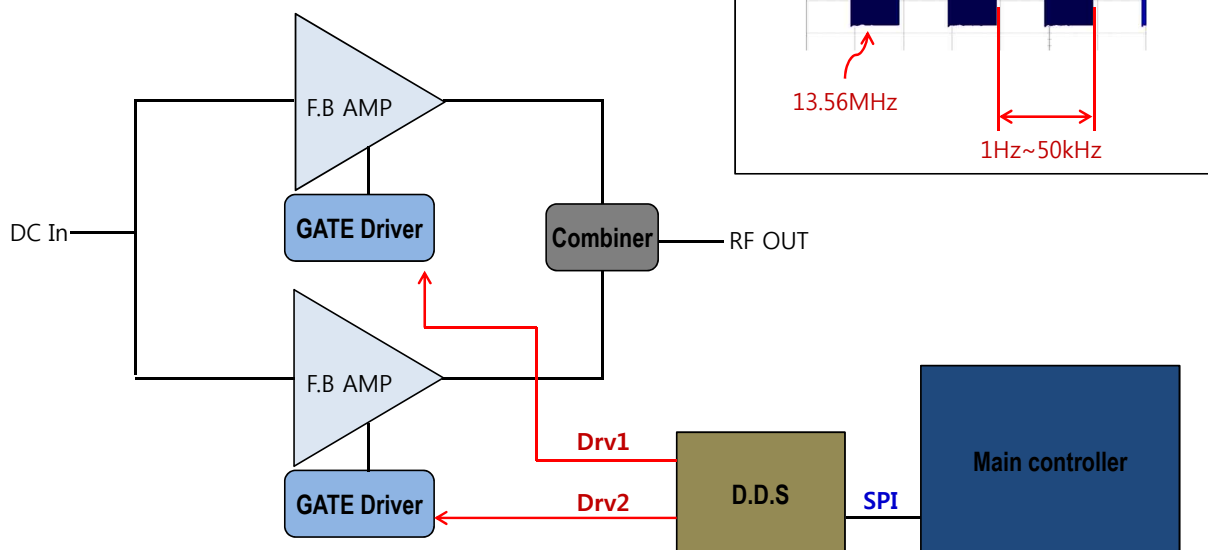
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DDS 구성

DDS(Direct Digital Synthesizer) 란?

13.56MHz 의 RF를 발생 시키기 위한 기준 신호
2개의 AMP 의 위상차를 이용해 출력제어에 사용



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RFG에서 DDS 구성

DDS 설계 사양

Frequency : 13.56MHz \pm 0.005%

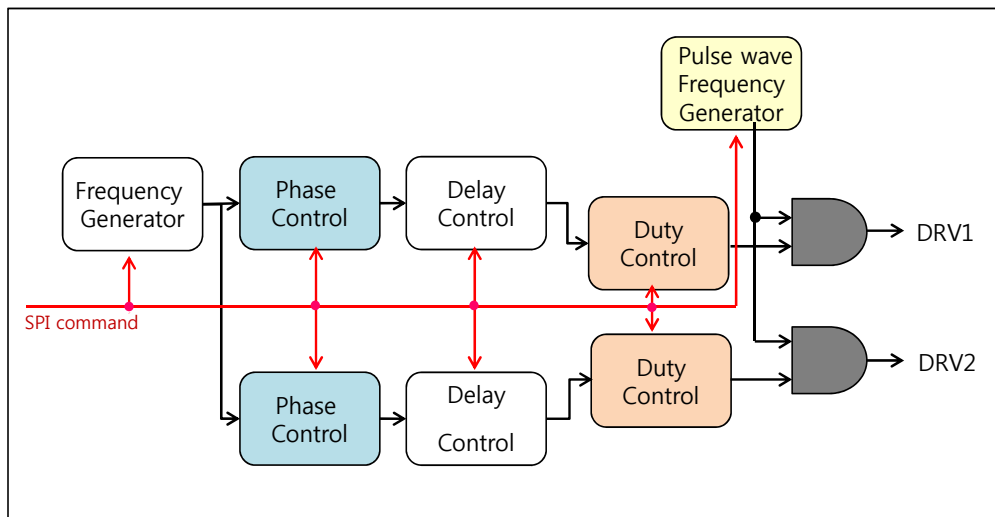
Main freq. Duty : 1 ~ 50%

Phase : 0deg ~ 180deg

Pulse freq : 1Hz ~ 50kHz

Pulse duty: 1~99% & CW

Timing resolution : 4ns



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구조 및 배치

Main controller

DSP Dual core x 2

DDS with FPGA

Interface

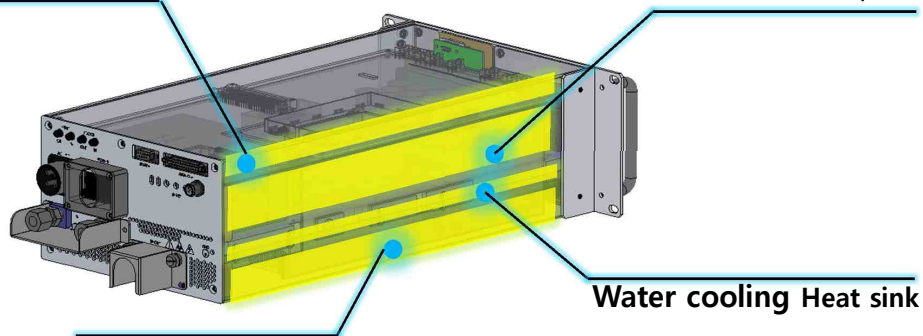
Power block

Single core DSP

Line noise filter

3.5kW DC/DC

400W sub DC/DC



R.F block

Dual Power AMP

RF gate Driver

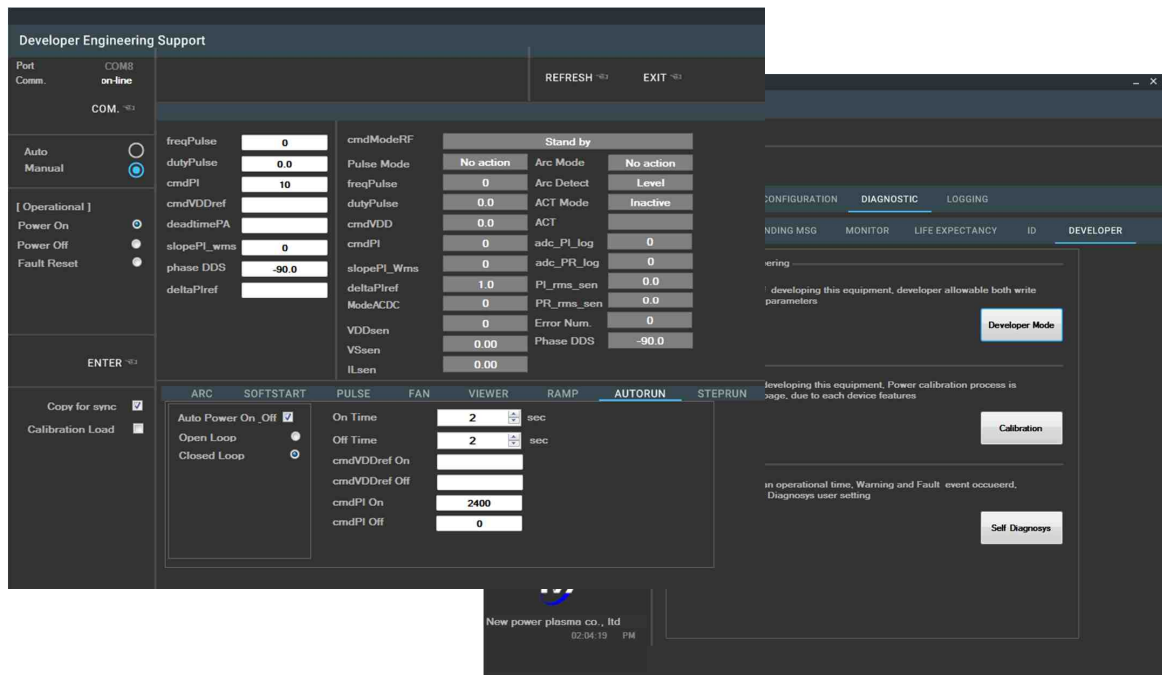
RF sensor

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U.I PC software



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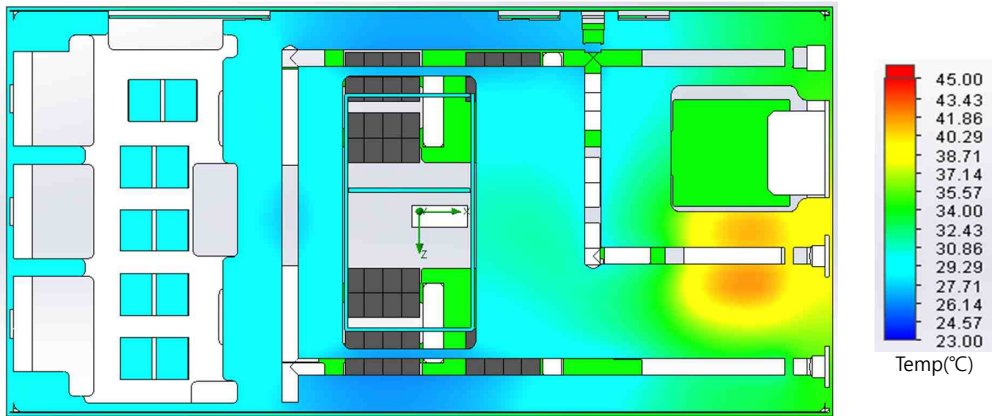
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열 해석

Water cooling heat sink simulation



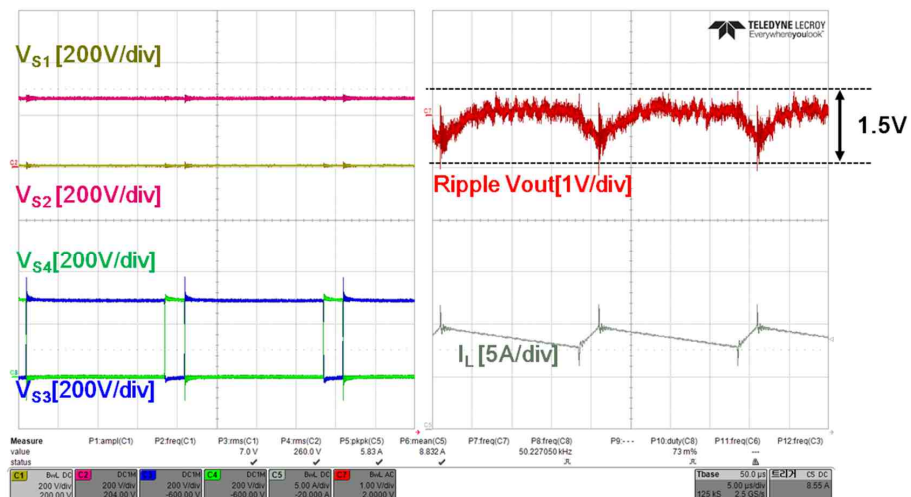
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실험 결과

DC/DC output ripple voltage



***V-ripple : 1.5V @300V(3.5kW) output**

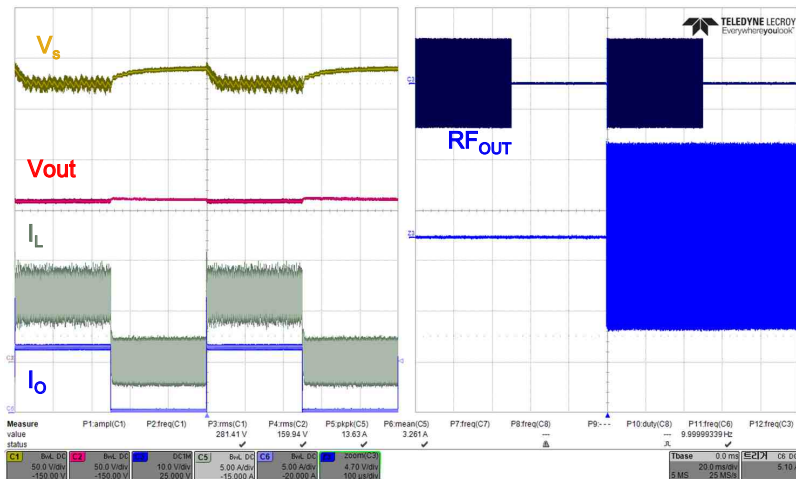
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실험 결과

DC/DC output @ pulse mode



*Fast response 동작 ,pulse output 대응

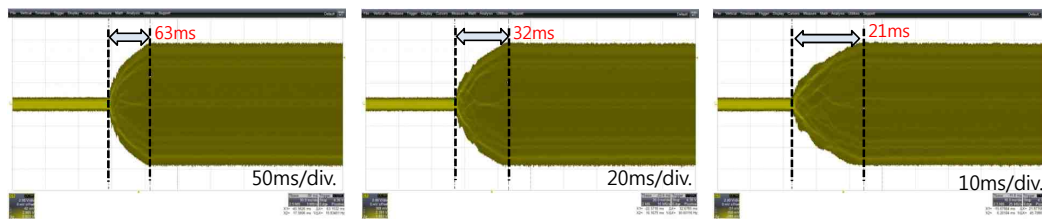
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실험 결과

Ramp up output



< 50w/ms >

ΔPower	3000 W
Slope	50 W/ms
Set	60 ms
Result	63 ms

< 100w/ms >

ΔPower	3000 W
Slope	100 W/ms
Set	30 ms
Result	32 ms

< 150w/ms >

ΔPower	3000 W
Slope	150 W/ms
Set	20 ms
Result	21 ms

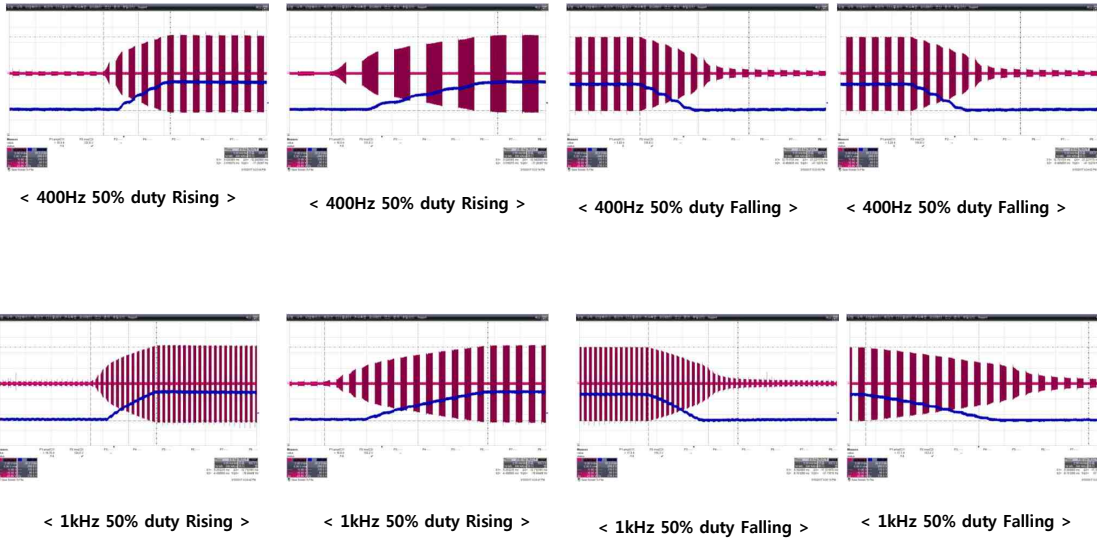
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실험 결과

Pulse output



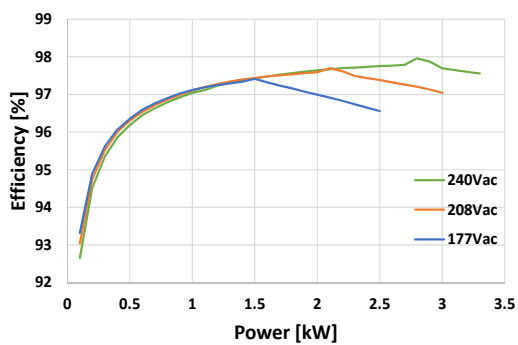
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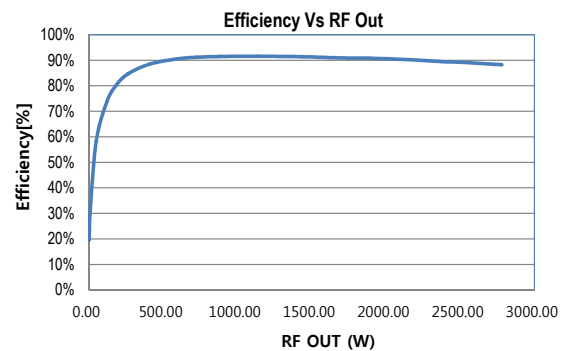
실험 결과

DC/DC



효율 : 95% 이상 달성

Power AMP



효율 : 88% 이상 달성

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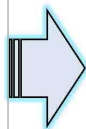
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RFG 기술의 발전 방향

차세대 RFG의 방향

- ◆ High power density
- ◆ Compact size
- ◆ Variable frequency output
- ◆ Automatic impedance matching
- ◆ mW Power control resolution
- ◆ Smart control



Power



- New topology 적용
- 전력 부품 소형화 기술
- 고 정밀 출력제어

RF



- 정밀 RF 출력 제어 기술
- 정밀 RF 출력 센싱 기술
- 자동 매칭 회로 개발

Digital control



- 고 정밀 출력 제어
- 수명 및 고장 예측
- 온도 및 부품 편차 자동 보상
- Plasma 공정 Monitoring

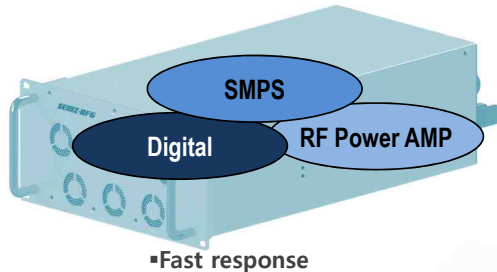
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RFG 적용 기술 응용 산업

RF Generator



- Fast response
- High accuracy
- Wide range output
- High power density
- High reliability
- Low noise

응용분야



산업용 유도 가열기
초음파 발생기



방산 장비
레이더
방송통신기기



의료기기
X-선 진단기
자기 공명 진단 기



신 재생 에너지
에너지 저장 장치
전기 자동차

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감사합니다.

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